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09/200430

	Subclass
Class	

ISSUE CLASSIFICATION

PATENT NUMBER

U.S. UTILITY Patent Application

O.I.P.E.

PATENT DATE

SCANNED  Q.A.

APPLICATION NO.	CONT/PRIOR	CLASS	SUBCLASS	ART UNIT	EXAMINER
09/928430	F	430	280	1752	LEE, S.J.

Applicants
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Positive-working photoresist composition and resist patterning method using same

PTO-2040
12/99

ISSUING CLASSIFICATION

ORIGINAL		CROSS REFERENCE(S)			
CLASS	SUBCLASS	CLASS	SUBCLASS (ONE SUBCLASS PER BLOCK)		
INTERNATIONAL CLASSIFICATION					

Continued on Issue Slip Inside File Jacket

TERMINAL DISCLAIMER	DRAWINGS			CLAIMS ALLOWED	
	Sheets Drwg.	Figs. Drwg.	Print Fig.	Total Claims	Print Claim for O.G.
<input type="checkbox"/> The term of this patent subsequent to _____ (date) has been disclaimed.				NOTICE OF ALLOWANCE MAILED	
<input type="checkbox"/> The term of this patent shall not extend beyond the expiration date of U.S Patent. No. _____				ISSUE FEE	
<input type="checkbox"/> The terminal _____ months of this patent have been disclaimed.				Amount Due	Date Paid
	(Assistant Examiner)	(Date)	(Primary Examiner)	(Date)	
	(Legal Instruments Examiner)	(Date)			ISSUE BATCH NUMBER

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